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Docket No. CL-2229 US NA
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In the Claims:

Please rewrite Claim 34. The requested amendments to Claim 34 are shown below on pages 3~10 of this paper in a marked-up version of that claim, as required by 37 CFR §1.121(c). Deletions are shown by strike-through, and additions are shown by underlining. A complete listing of all claims indicating the status thereof is also shown on pages 3~10.

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Listing of Claims

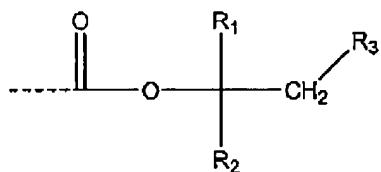
[including (i) amendments to Claim 34, and
(ii) status of all claims
(Claims 25~44 remain active)]

1~24. (canceled).

25. (previously presented) In an electronic device that comprises a substrate having conductive properties, a process for fabricating a protective layer, comprising

(a) applying to the substrate a protective layer composition to form a protective layer thereon, wherein the protective layer composition comprises a polymer comprising, as polymerized units, monomers of which at least 50 mole percent comprise a structure selected from the group consisting of:

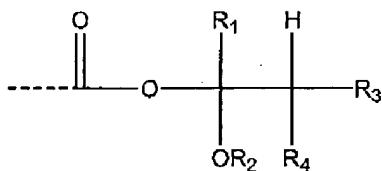
(I)



wherein R₁ is hydrogen or lower alkyl, R₂ is lower alkyl, and R₃ is hydrogen or lower alkyl; wherein lower alkyl includes alkyl groups having 1 to 6 linear or cyclic carbon atoms;

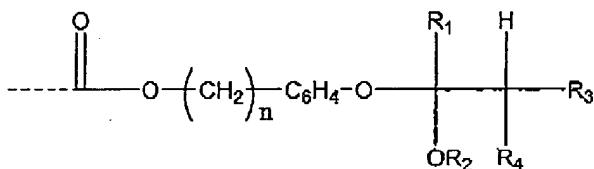
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(II)



wherein R₁ is hydrogen or lower alkyl, R₂ is lower alkyl, and R₃ and R₄ are independently hydrogen or lower alkyl; wherein lower alkyl includes alkyl groups having 1 to 6 carbon atoms, and the joining of R₁ and R₂, or R₁ and either R₃ or R₄, or R₂ and either R₃ or R₄ to form a 5-, 6-, or 7-membered ring;

(III)



wherein R₁ is hydrogen or lower alkyl, R₂ is lower alkyl, and R₃ and R₄ are independently hydrogen or lower alkyl; wherein lower alkyl includes alkyl groups having 1 to 6 carbon atoms, and the joining of R₁ and R₂, or R₁ and either R₃ or R₄, or R₂ and either R₃ or R₄ to form a 5-, 6-, or 7-membered ring; and n is 0 to 4; and (IV) mixtures of (I), (II) and/or (III);

- (b) irradiating the protective layer through a mask;
- (c) heating the device;

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(d) contacting the protective layer with a developing solution to remove the portions of the protective layer composition exposed to radiation in step (b) and form a patterned protective layer;

(e) irradiating the patterned protective layer; and

(f) heating the device.

26. (previously presented) The process of Claim 25 wherein the protective layer composition comprises a polymer comprising, as polymerized units, monomers of which at least 60 mole percent comprise a structure selected from the group consisting of (I), (II), (III) and (IV).

27. (previously presented) The process of Claim 25 wherein the protective layer composition comprises a polymer comprising, as polymerized units, a monomer selected from the group consisting of 1-ethoxyethyl methacrylate (or acrylate), 1-butoxyethyl methacrylate (or acrylate), 1-ethoxy-1-propyl methacrylate (or acrylate), tetrahydropyranyl methacrylate (or acrylate), tetrahydropyranyl p-vinylbenzoate, 1-ethoxy-1-propyl p-vinylbenzoate, 4-(2-tetrahydropyranyloxy)benzyl methacrylate (or acrylate), 4-(1-butoxyethoxy)benzyl methacrylate (or acrylate); and mixtures thereof.

28. (previously presented) The process of Claim 25 wherein the protective layer composition comprises a polymer comprising, as a polymerized unit, a monomer selected from the group consisting of t-butyl methacrylate (or acrylate); neopentyl methacrylate (or acrylate); 1-bicyclo{2,2,2}octyl methacrylate (or acrylate) and their derivatives; 1-bicyclo{2,2,1}heptyl methacrylate (or acrylate) and their derivatives; 1-bicyclo{2,1,1}hexyl methacrylate (or acrylate) and their derivatives; 1-bicyclo{1,1,1}pentyl methacrylate (or acrylate) and their derivatives; 1-

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adamantyl methacrylate (or acrylate) and their derivatives; and mixtures thereof.

29. (previously presented) The process of Claim 25 wherein the protective layer composition comprises a polymer comprising, as a polymerized unit, up to about 10 mole percent of a monomer selected from methyl methacrylate, methyl acrylate, methacrylic acid, and hydroxyl ethyl methacrylate; and mixtures thereof.

30. (previously presented) The process of Claim 25 wherein the protective layer composition comprises 0.5-30 mole% of photoacid generator and 10-1000 ppm of photosensitizer.

31. (previously presented) The process of Claim 25 wherein the protective layer composition has a molecular weight in the range of about 7,000 to about 1,000,000.

32. (previously presented) The process of Claim 25 wherein the protective layer composition comprises a copolymer.

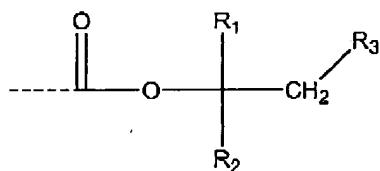
33. (previously presented) The process of Claim 25 wherein the protective layer composition comprises a polymer comprising, as a polymerized unit, a monomer having a hydrophilic group.

34. (currently amended) A process for fabricating an electronic device that comprises a substrate having conductive properties, comprising
| (a) applying to a first side of the substrate a protective layer composition to form a protective layer thereon, wherein the protective layer composition comprises a polymer comprising, as polymerized units,

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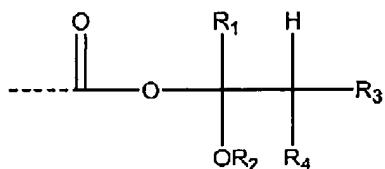
monomers of which at least 50 mole percent comprise a structure selected from the group consisting of:

(I)



wherein R₁ is hydrogen or lower alkyl, R₂ is lower alkyl, and R₃ is hydrogen or lower alkyl; wherein lower alkyl includes alkyl groups having 1 to 6 linear or cyclic carbon atoms;

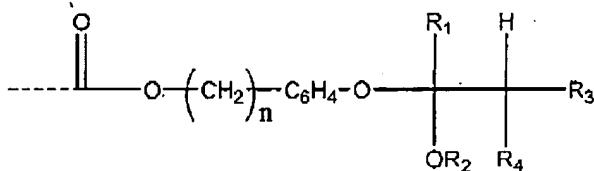
(II)



wherein R₁ is hydrogen or lower alkyl, R₂ is lower alkyl, and R₃ and R₄ are independently hydrogen or lower alkyl; wherein lower alkyl includes alkyl groups having 1 to 6 carbon atoms, and the joining of R₁ and R₂, or R₁ and either R₃ or R₄, or R₂ and either R₃ or R₄ to form a 5-, 6-, or 7-membered ring;

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(III)



wherein R₁ is hydrogen or lower alkyl, R₂ is lower alkyl, and R₃ and R₄ are independently hydrogen or lower alkyl; wherein lower alkyl includes alkyl groups having 1 to 6 carbon atoms, and the joining of R₁ and R₂, or R₁ and either R₃ or R₄, or R₂ and either R₃ or R₄ to form a 5-, 6-, or 7-membered ring; and n is 0 to 4; and (IV) mixtures of (I), (II) and/or (III);

- (b) irradiating the protective layer through a mask;
- (c) heating the device;
- (d) contacting the protective layer with a developing solution to remove the portions of the protective layer composition exposed to radiation in step (b) and form a patterned protective layer;
- (e) irradiating the patterned protective layer;
- (f) heating the device;
- (g) applying to the patterned protective layer a paste composition;
- (h) irradiating the device from the ~~backside~~ a second side of the substrate to form a pattern in the paste composition; and
- (i) contacting the paste composition and the patterned protective layer with a developing solution to remove (I) the portions of the paste composition not exposed to radiation in step (h), and (II) the patterned protective layer.

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35. (previously presented) The process of Claim 34 wherein the protective layer composition comprises a polymer comprising, as polymerized units, monomers of which at least 60 mole percent comprise a structure selected from the group consisting of (I), (II), (III) and (IV).

36. (previously presented) The process of Claim 34 wherein the protective layer composition comprises a polymer comprising, as polymerized units, a monomer selected from the group consisting of 1-ethoxyethyl methacrylate (or acrylate), 1-butoxyethyl methacrylate (or acrylate), 1-ethoxy-1-propyl methacrylate (or acrylate), tetrahydropyranyl methacrylate (or acrylate), tetrahydropyranyl p-vinylbenzoate, 1-ethoxy-1-propyl p-vinylbenzoate, 4-(2-tetrahydropyranyloxy)benzyl methacrylate (or acrylate), 4-(1-butoxyethoxy)benzyl methacrylate (or acrylate); and mixtures thereof.

37. (previously presented) The process of Claim 34 wherein the protective layer composition comprises a polymer comprising, as a polymerized unit, a monomer selected from the group consisting of t-butyl methacrylate (or acrylate); neopentyl methacrylate (or acrylate); 1-bicyclo{2,2,2}octyl methacrylate (or acrylate) and their derivatives; 1-bicyclo{2,2,1}heptyl methacrylate (or acrylate) and their derivatives; 1-bicyclo{2,1,1}hexyl methacrylate (or acrylate) and their derivatives; 1-bicyclo{1,1,1}pentyl methacrylate (or acrylate) and their derivatives; 1-adamantyl methacrylate (or acrylate) and their derivatives; and mixtures thereof.

38. (previously presented) The process of Claim 34 wherein the protective layer composition comprises a polymer comprising, as a polymerized unit, up to about 10 mole percent of a monomer selected from,

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methyl methacrylate, methyl acrylate, methacrylic acid, and hydroxyl ethyl methacrylate; and mixtures thereof.

39. (previously presented) The process of Claim 34 wherein the protective layer composition comprises 0.5-30 mole% of photoacid generator and 10-1000 ppm of photosensitizer.

40. (previously presented) The process of Claim 34 wherein the protective layer composition has a molecular weight in the range of about 7,000 to about 1,000,000.

41. (previously presented) The process of Claim 34 wherein the protective layer composition comprises a copolymer.

42. (previously presented) The process of Claim 34 wherein the protective layer composition comprises a polymer comprising, as a polymerized unit, a monomer having a hydrophilic group.

43. (previously presented) The process of Claim 34 wherein the paste composition comprises silver.

44. (previously presented) The process of Claim 34 wherein the paste composition comprises carbon nanotubes.